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APPLICATION NO.	FILING DATE	FIRST NAMED INVENTOR	ATTORNEY DOCKET NO.	CONFIRMATION NO.
09/882,141	06/15/2001	Yiqiong Wang	AM1562D1	8856 18
32588	7590	08/27/2003		
APPLIED MATERIALS, INC. 2881 SCOTT BLVD. M/S 2061 SANTA CLARA, CA 95050			EXAMINER	
			UMEZ ERONINI, LYNETTE T	
		ART UNIT	PAPER NUMBER	
		1765		

DATE MAILED: 08/27/2003

Please find below and/or attached an Office communication concerning this application or proceeding.

Office Action Summary	Application No.	Applicant(s)
	09/882,141	WANG ET AL.
	Examiner	Art Unit
	Lynette T. Umez-Eronini	1765

-- The MAILING DATE of this communication appears on the cover sheet with the correspondence address --

Period for Reply

A SHORTENED STATUTORY PERIOD FOR REPLY IS SET TO EXPIRE 3 MONTH(S) FROM THE MAILING DATE OF THIS COMMUNICATION.

- Extensions of time may be available under the provisions of 37 CFR 1.136(a). In no event, however, may a reply be timely filed after SIX (6) MONTHS from the mailing date of this communication.
- If the period for reply specified above is less than thirty (30) days, a reply within the statutory minimum of thirty (30) days will be considered timely.
- If NO period for reply is specified above, the maximum statutory period will apply and will expire SIX (6) MONTHS from the mailing date of this communication.
- Failure to reply within the set or extended period for reply will, by statute, cause the application to become ABANDONED (35 U.S.C. § 133).
- Any reply received by the Office later than three months after the mailing date of this communication, even if timely filed, may reduce any earned patent term adjustment. See 37 CFR 1.704(b).

Status

1) Responsive to communication(s) filed on 6-12-03

2a) This action is FINAL. 2b) This action is non-final.

3) Since this application is in condition for allowance except for formal matters, prosecution as to the merits is closed in accordance with the practice under *Ex parte Quayle*, 1935 C.D. 11, 453 O.G. 213.

Disposition of Claims

4) Claim(s) 11-14 is/are pending in the application.

4a) Of the above claim(s) _____ is/are withdrawn from consideration.

5) Claim(s) _____ is/are allowed.

6) Claim(s) 11-14 is/are rejected.

7) Claim(s) _____ is/are objected to.

8) Claim(s) _____ are subject to restriction and/or election requirement.

Application Papers

9) The specification is objected to by the Examiner.

10) The drawing(s) filed on _____ is/are: a) accepted or b) objected to by the Examiner.
Applicant may not request that any objection to the drawing(s) be held in abeyance. See 37 CFR 1.85(a).

11) The proposed drawing correction filed on _____ is: a) approved b) disapproved by the Examiner.
If approved, corrected drawings are required in reply to this Office action.

12) The oath or declaration is objected to by the Examiner.

Priority under 35 U.S.C. §§ 119 and 120

13) Acknowledgment is made of a claim for foreign priority under 35 U.S.C. § 119(a)-(d) or (f).
a) All b) Some * c) None of:
1. Certified copies of the priority documents have been received.
2. Certified copies of the priority documents have been received in Application No. _____.
3. Copies of the certified copies of the priority documents have been received in this National Stage application from the International Bureau (PCT Rule 17.2(a)).
* See the attached detailed Office action for a list of the certified copies not received.

14) Acknowledgment is made of a claim for domestic priority under 35 U.S.C. § 119(e) (to a provisional application).
a) The translation of the foreign language provisional application has been received.

15) Acknowledgment is made of a claim for domestic priority under 35 U.S.C. §§ 120 and/or 121.

Attachment(s)

1) Notice of References Cited (PTO-892) 4) Interview Summary (PTO-413) Paper No(s). _____.
2) Notice of Draftsperson's Patent Drawing Review (PTO-948) 5) Notice of Informal Patent Application (PTO-152)
3) Information Disclosure Statement(s) (PTO-1449) Paper No(s) _____. 6) Other:

DETAILED ACTION

Claim Rejections - 35 USC § 112

1. The following is a quotation of the second paragraph of 35 U.S.C. 112:

The specification shall conclude with one or more claims particularly pointing out and distinctly claiming the subject matter which the applicant regards as his invention.

2. Claim 14 is rejected under 35 U.S.C. 112, second paragraph, as being indefinite for failing to particularly point out and distinctly claim the subject matter which applicant regards as the invention.

In claim 14, "the volume ratio of hydrogen bromide to sulfur hexafluoride and oxygen is 0.1 to 10" is indefinite because it is unclear which components of the etchant mixture are being compared. Is the ratio of HBr:SF₆ and of HBr:O₂ 0.1 to 10?

3. In claims 13 and 14, "the volume ratio" lacks antecedent basis.

Claim Rejections - 35 USC § 102

4. The following is a quotation of the appropriate paragraphs of 35 U.S.C. 102 that form the basis for the rejections under this section made in this Office action:

A person shall be entitled to a patent unless –

(b) the invention was patented or described in a printed publication in this or a foreign country or in public use or on sale in this country, more than one year prior to the date of application for patent in the United States.

5. Claims 11 and 12 are rejected under 35 U.S.C. 102(b) as being anticipated by Komura (US 5,423,941).

Komura teaches etching a silicon semiconductor substrate with an etchant gas mixture comprising HBr, SiF₄, He (same as applicant's noble gas), O₂, and SF₆ (Figure 1A; column 4 line 23-27; column 6, lines 49-52, 63-66; Tables 1, 2, 3, and 6; Figure 3; and column 4, lines 8-24), which reads on,

A etchant wherein the plasma is formed from a gaseous mixture of hydrogen bromide, oxygen, and sulfur hexafluoride, **in claim 11**; and
wherein said gaseous mixture further includes a noble gas, **as in claim 12**.

Since Komura's etchant mixture is the same as that of the claimed invention, then using Komura's etchant mixture in the same manner as in the claimed invention would inherently result in: A plasma anisotropic etchant for a silicon-containing substrate mounted on a substrate electrode in a plasma etch chamber, said plasma formed between two electrodes in a vacuum chamber, the first electrode comprising a gas inlet electrode and the second electrode comprising an RF powered substrate electrode, that etches deep, straight walled, rounded bottom openings in silicon, **as in claim 11**.

Claim Rejections - 35 USC § 103

6. The following is a quotation of 35 U.S.C. 103(a) which forms the basis for all obviousness rejections set forth in this Office action:

(a) A patent may not be obtained though the invention is not identically disclosed or described as set forth in section 102 of this title, if the differences between the subject matter sought to be patented and the prior art are such that the subject matter as a whole would have been obvious at the time the invention was made to a person having ordinary skill in the art to which said subject matter pertains. Patentability shall not be negated by the manner in which the invention was made.

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7. Claims 13 and 14 are rejected under 35 U.S.C. 103(a) as being unpatentable over Komura ('941) as applied to claim 11 above, and further in view of in view of Kuyel (US 4,496,425).

Komura differs only in failing to specify the volume ratio of hydrogen bromide to sulfur hexafluoride is 0.1 to 10, **in claim 13**; and of hydrogen bromide to sulfur hexafluoride and oxygen is 0.1 to 10, **in claim 14**.

Kuyel teaches, "Plasma etching is controlled by a number of parameters including the nature of the etching gas, the RF power level used, the gas flow rate and chamber pressure, the temperature, and the load or volume of material to be etched. Because of the many variables, empirically setting process specifications and obtaining run-to-run reproducibility has been very difficult" (column 1, lines 19-25), which provides evidence that the volume, which is known to be directly proportional to flow rate, is a so-called "result effective variable."

It is the examiner's position that it would have been obvious to one having ordinary skill in the art at the time of the claimed invention to modify Komura by using Kuyel's method of varying the flow rate (which is proportional to the volume) of gases since it has been held that discovering an optimum value of a result effective variable involves only routine skill in the art. *In re Boesch*, 617 f.2d 272, 205 USPQ 215 (CCPA 1980).

Conclusion

8. Applicant's amendment necessitated the new ground(s) of rejection presented in this Office action. Accordingly, **THIS ACTION IS MADE FINAL**. See MPEP

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§ 706.07(a). Applicant is reminded of the extension of time policy as set forth in 37 CFR 1.136(a).

A shortened statutory period for reply to this final action is set to expire THREE MONTHS from the mailing date of this action. In the event a first reply is filed within TWO MONTHS of the mailing date of this final action and the advisory action is not mailed until after the end of the THREE-MONTH shortened statutory period, then the shortened statutory period will expire on the date the advisory action is mailed, and any extension fee pursuant to 37 CFR 1.136(a) will be calculated from the mailing date of the advisory action. In no event, however, will the statutory period for reply expire later than SIX MONTHS from the date of this final action.

Any inquiry concerning this communication or earlier communications from the examiner should be directed to Lynette T. Umez-Eronini whose telephone number is 703-306-9074. The examiner is normally unavailable on the First Friday.

If attempts to reach the examiner by telephone are unsuccessful, the examiner's supervisor, Nadine Norton can be reached on 703-305-2667. The fax phone number for the organization where this application or proceeding is assigned is (703) 872-9306.

Itue

August 14, 2003

NADINE G. NORTON
PRIMARY EXAMINER

